

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: Seiichi NAGATA) Confirmation No.: 4585
U.S. Application No.: 10/551,195) Group Art Unit: Unassigned
Filed: September 29, 2005) Examiner: Unassigned

For: SILICON SUBSTRATE AND METHOD OF FORMING THE SAME

Commissioner for Patents
U.S. Patent and Trademark Office
Customer Window Mail Stop: PCT
Alexandria, VA 22314

Sir:

INFORMATION DISCLOSURE STATEMENT (IDS)

Under 37 C.F.R. § 1.97(b): Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), Applicant brings to the attention of the Examiner the documents listed on the attached PTO Form 1449. To the undersigned's knowledge, this IDS is being filed before the mailing date of a first Office Action on the merits, before the mailing date of a first Office Action on the merits after filing an RCE under § 1.114, or within three months of the application filing date.

Under 37 C.F.R. § 1.97(c): Pursuant to 37 C.F.R. §§ 1.56 and 1.97(c), Applicant brings to the attention of the Examiner the documents listed on the attached PTO Form 1449. This IDS is being filed after the events recited in § 1.97(b) but, to the undersigned's knowledge, before the mailing date of a Final Office Action, a Notice of Allowance, or another action that closes prosecution in the application.

- The fee of \$180.00 set forth in § 1.17(p) is included herein; or
- Applicant submits that each item of information contained in this IDS was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this IDS.

Under 37 C.F.R. § 1.97(d): Pursuant to 37 C.F.R. §§ 1.56 and 1.97(d), Applicant brings to the attention of the Examiner the documents listed on the attached PTO Form 1449. This IDS is being filed after the events recited in § 1.97(c) but before payment of the issue fee.

- The fee of \$180.00 set forth in § 1.17(p) is included herein; and
- Applicant submits that each item of information contained in this IDS was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this IDS.

Under 37 C.F.R. § 1.97(i): Pursuant to 37 C.F.R. §§ 1.56 and 1.97(i), Applicant brings to the attention of the Examiner the documents listed on the attached PTO Form 1449. This IDS is being filed after the events recited in § 1.97(d). Applicant requests that the IDS be placed in the file.

A search report or other listing of documents from a counterpart, related, or other application dated July 6, 2004 and having documents cited thereon is attached for the Examiner's consideration. Any of these documents not previously cited, and any additional documents are listed on the PTO Form 1449.

Applicant respectfully requests that the Examiner consider the listed documents and evidence that consideration by making appropriate notations on the attached form. As for any document listed on the accompanying PTO-1449 that is in a language other than English, relevance can be understood from an enclosed English abstract or at least partial translation or from mention in the specification or in a search report for a corresponding application.

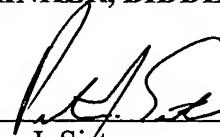
This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that any of the listed documents are material or constitute "prior art." If it should be determined that any of the listed documents do not constitute "prior art" under United States law, Applicant reserve the right to present to the Office the relevant facts and law regarding the appropriate status of such documents.

Applicant further reserves the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should any of the documents be applied against the claims of the present application.

Except for issue fees payable under 37 C.F.R. § 1.18, the Commissioner is hereby authorized by this paper to charge any additional fees during the entire pendency of this Application, including fees due under 37 C.F.R. § 1.16 and 1.17 which may be required and including any required extension of time fees, or credit any overpayment to Deposit Account No. 50-0573. This paragraph is intended to be a CONSTRUCTIVE PETITION FOR EXTENSION OF TIME in accordance with 37 C.F.R. § 1.136(a)(3).

Respectfully submitted,

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Dated: July 17, 2006

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INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)		Attorney Docket No.: 46884-5429	Serial No.: 10/551,195		
PTO Form 1449		Applicants: Seiichi NAGATA	Page 1 of 1		
		Filing Date: September 29, 2005	Group Art Unit: Unassigned		
U.S. PATENT DOCUMENTS					
*Examiner Initial	Document Number	Date	Name	Class	Sub Class
FOREIGN PATENT DOCUMENTS					
	Document Number	Date	Country	Class	Sub Class
	10-133047	May 22, 1998	JP		Abstract
	11-242125	Sept. 7, 1999	JP		Abstract
	2000-047045	Feb. 18, 2000	JP		Abstract
	11-014848	Jan. 22, 1999	JP		Abstract
	10-160950	Jun. 19, 1998	JP		Abstract
	10-133048	May 22, 1998	JP		Abstract
	10-300963	Nov. 13, 1998	JP		Abstract
	61-180449	Aug. 13, 1986	JP		Abstract
	52-063685	May 26, 1977	JP		Abstract
	09-292540	Nov. 11, 1997	JP		Abstract
OTHER DOCUMENTS (Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.) date, page(s), volume-issue number(s), publisher, city and/or country where published.)					
	M.E. Lines, "Can The Minimum Attenuation of Fused Silica Be Significantly Reduced By Small Compositional Variations? I. Alkali Metal Dopants"; Journal of Non-Crystalline Solids 171, 1994, pp. 209-218				
	M.E. Lines, "Can The Minimum Attenuation Of Fused Silica Be Significantly Reduced By Small Compositional Variations? II. Combined Fluorine and Alkali Metal Dopants", Journal of Non-Crystalline Solids 171, 1994, pp. 219-227				
	K. SAITO et al., "A New Method of Developing Ultralow-Loss Glasses", J. Appl. Phys. 81 (11), June 1, 1997, pp. 7129-7134				
	Fumiaki HANAWA et al., "Fabrication of Pure Silica Core Fibers By VAD Method", Transactions of the Institute of Electronics and Communication Engineers of Japan, Part C, Vol. J68C, No. 8, Aug. 1985, pp. 597-604, including English language abstract				
	Fumiaki HANAWA et al., "Fluorine-doping Mechanism For Silica Glass Particles", Transactions of the Institute of Electronics, Information and Communication Engineers C, Vol. J71C, No. 2, Feb. 1988, pp. 212-220, including English language abstract				
	M. KYOTO et al., "Characterization of Fluorine-doped Silica Glasses", Journal of Materials Science 28, 1993, pp. 2738-2744				
	P.K. BACHMANN et al., "Thermal Expansion Coefficients of Doped And Undoped Silica Prepared By Means Of PCVD", Journal of Materials Science 23, 1988, pp. 2584-2588				
	K. KOBAYASHI, "Structural Interpretation Of The Low Temperature Reflow Of Borophosphosilicate Glasses Doped With BF ₂ By Ion Implantation", Glass Technology, Vol. 29, No. 6, December 1988, pp. 253-257				
	Hiroshi TANAKA et al., "Sintering Temperature of Porous Glass And Transition Temperature Of High Silica Glass", Yogyo-Kyokai-Shi, Vol. 94, No. 6, 1986, pp. 564-570, including English language abstract				
	Morio TAKAHASHI et al., "Fabrication and Characteristics Of Three-Dimensionally Buried Porous Silicon Optical Waveguides", Journal of Applied Physics, Vol. 86, No. 9, November 1, 1999, pp. 5274-5278				
	Gabriella MAIELLO et al., "Light Guiding In Oxidised Porous Silicon Optical Waveguides", Thin Solid Films 297, 1997, pp. 311-313				
	V.P. BONDARENKO et al., "Optical Waveguide Based On Oxidized Porous Silicon", Microelectronic Engineering 28, 1995, pp. 447-450				
Examiner			Date Considered		
Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.					